

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2	"20060175191".pn.	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/04/27 10:10
L5	475	(205/661,663.ccls.)	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/04/27 10:25
L7	1	(205/661,663.ccls.) and (ion adj exchang\$3 near (member membrane))	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/04/27 10:26
L9	48	((ion adj exchang\$3) (membrane)) with (electrolytic electrolytically electrochemical electrochemically) near3 (process process\$3 polish polish\$3 planariz\$3 planarization) and (CMP ((chemical chemically) adj (mechanical mechanically) adj (polish polish\$3 process process\$3 planariz\$3 planarization)))	US_PGPUB	OR	ON	2009/04/27 10:27
S1	2	"6328872".pn.	US_PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 11:13
S2	9372	((ion adj exchang\$3) (membrane)) and (electrolytic electrolytically electrochemical electrochemically) near3 (process process\$3 polish polish\$3 planariz\$3 planarization)	US_PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 11:35

S3	9372	((ion adj exchang\$3) (membrane)) and (electrolytic electrolytically electrochemical electrochemically) near3 (process process\$3 polish polish\$3 planariz\$3 planarization) and ((pd< "20030319") (ad< "20030319"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 11:41
S4	6819	((ion adj exchang\$3) (membrane)) and (electrolytic electrolytically electrochemical electrochemically) near3 (process process\$3 polish polish\$3 planariz\$3 planarization) and ((@pd< "20030319") (@ad< "20030319"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 11:45
S5	6819	((ion adj exchang\$3) (membrane)) and (electrolytic electrolytically electrochemical electrochemically) near3 (process process\$3 polish polish\$3 planariz\$3 planarization) and ((@pd< "20030319") (@ad< "20030319"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 11:48
S6	6819	((ion adj exchang\$3) (membrane)) and (electrolytic electrolytically electrochemical electrochemically) near3 (process process\$3 polish polish\$3 planariz\$3 planarization) and ((@pd< "20030319") (@ad< "20030319"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 11:48
S7	5546	((ion adj exchang\$3) (membrane)) and (electrolytic electrolytically electrochemical electrochemically) near3 (process process\$3 polish polish\$3 planariz\$3 planarization) and (@pd< "20030319")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 11:49

S8	2170	((ion adj exchang\$3) (membrane)) same (electrolytic electrolytically electrochemical electrochemically) near3 (process process\$3 polish polish\$3 planariz\$3 planarization) and (@pd< "20030319")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 11:50
S9	1231	((ion adj exchang\$3) (membrane)) with (electrolytic electrolytically electrochemical electrochemically) near3 (process process\$3 polish polish\$3 planariz\$3 planarization) and (@pd< "20030319")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 11:51
S10	3	((ion adj exchang\$3) (membrane)) with (electrolytic electrolytically electrochemical electrochemically) near3 (process process\$3 polish polish\$3 planariz\$3 planarization) and (@pd< "20030319") and (CMP ((chemical chemically) adj (mechanical mechanically) adj (polish polish\$3 process process\$3 planariz\$3 planarization)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 11:52
S11	50	((ion adj exchang\$3) (membrane)) same (electrolytic electrolytically electrochemical electrochemically) near3 (process process\$3 polish polish\$3 planariz\$3 planarization) and (@pd< "20030319") and (CMP ((chemical chemically) adj (mechanical mechanically) adj (polish polish\$3 process process\$3 planariz\$3 planarization)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 11:53

S12	34	((ion adj exchang\$3) (membrane)).clm. and (electrolytic electrolytically electrochemical electrochemically) near3 (process process\$3 polish polish\$3 planariz\$3 planarization).clm. and (@pd< "20030319") and (mechanical CMP mechanically pad slurry).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 11:59
S13	34	((ion adj exchang\$3) (membrane)).clm. and (electrolytic electrolytically electrochemical electrochemically) near3 (process process\$3 polish polish\$3 planariz\$3 planarization).clm. and (@pd< "20030319") and (mechanical CMP mechanically pad slurry).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 12:00
S14	5	((ion adj exchang\$3) near2 (membrane)).clm. and (electrolytic electrolytically electrochemical electrochemically) near3 (process process\$3 polish polish\$3 planariz\$3 planarization).clm. and (@pd< "20030319") and (mechanical CMP mechanically pad slurry).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 12:03
S15	0	((ion adj exchang\$3) near2 (membrane)).clm. and (electrolytic electrolytically electrochemical electrochemically) near3 (process process\$3 polish polish\$3 planariz\$3 planarization).clm. and (@pd< "20030319").clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 12:04
S16	64	((ion adj exchang\$3) near2 (membrane)).clm. and (electrolytic electrolytically electrochemical electrochemically) near3 (process process\$3 polish polish\$3 planariz\$3 planarization).clm. and (@pd< "20030319")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 12:04

S17	6	((ion adj exchang\$3) near2 (membrane)).clm. and (205/640-686.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 12:06
S18	855	((ion adj exchang\$3) near2 (membrane)).clm. and ("204" "205").clas.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 12:07
S19	58	((ion adj exchang\$3) near2 (membrane)).clm. and ("204" "205").clas. and (polish polish \$3 planariz\$3 planarization)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 12:07
S20	353	((ion adj exchang\$3) catalyst (pure adj water)).clm. and ("204" "205").clas. and (polish polish\$3 planariz\$3 planarization)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 12:21
S21	23	((ion adj exchang\$3) catalyst (pure adj water)).clm. and ("204" "205").clas. and (polish polish\$3 planariz\$3 planarization) with (pure adj water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 12:21
S22	243	((ion adj exchang\$3) catalyst (pure adj water)).clm. and (polish polish\$3 planariz\$3 planarization) with (pure adj water)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 12:22
S23	100	((ion adj exchang\$3) catalyst (pure adj water)).clm. and (polish polish\$3 planariz\$3 planarization process process \$3) with (pure adj water) and (electrolytic electrolytically electrochemical electrochemically) near2 (polish polish\$3 planariz\$3 planarization process process \$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 12:23

S24	47	((ion adj exchang\$3) catalyst (pure adj water)).clm. and (polish polish\$3 planariz\$3 planarization process process \$3) with (pure adj water) and ((electrolytic electrolytically electrochemical electrochemically) near2 (polish polish\$3 planariz\$3 planarization process process \$3)).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 12:24
S25	100	((ion adj exchang\$3) catalyst (pure adj water)).clm. and (polish polish\$3 planariz\$3 planarization process process \$3) with (pure adj water) and ((electrolytic electrolytically electrochemical electrochemically) near2 (polish polish\$3 planariz\$3 planarization process process \$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 12:24
S26	157	((ion adj exchang\$3) catalyst) and (pure adj water) and (polish polish\$3 planariz \$3 planarization process process\$3) with (pure adj water) and ((electrolytic electrolytically electrochemical electrochemically) near2 (polish polish\$3 planariz\$3 planarization process process \$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 12:25
S27	4	"2002047139"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 13:14
S28	6	2002-126400	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 14:05
S29	2	"2002126400"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 14:05

S30	6	"2002012640"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 14:06
S31	15	2002-000838	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 14:06
S32	3	"20030132103"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/05/26 14:10
S33	2587	(electrode) near2 (spaced near2 apart) and (microelectronic workpiece wafer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/15 13:57
S34	185	((electrode) near2 (spaced near2 apart)) and (microelectronic workpiece wafer) and (electrolytic electrolytically electroprocess electroprocess\$3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/15 13:58
S35	246	(abrasive near2 particle) with (micron) and (CMP)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/15 14:29
S36	4	"7101465".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/15 14:41

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